

Fabrication of ultrathin nanostructures on the flexible substrates via secondary sputtering phenomenon and its application in flexible transparent conducting films

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We present a simple nanopatterning method for flexible substrates with high resolution and a high aspect ratio over a large area that uses the secondary sputtering phenomenon (SSP) and no solvents at room temperature and low pressures, and characterize flexible and transparent conducting films prepared with SSP that have performances comparable to that of ITO films yet higher mechanical stability